

Figure 1 – Schematic of fabricated test structures on (a) $\beta\text{-Ga}_2\text{O}_3$ (b) $\beta\text{-(Al}_x\text{Ga}_{1-x})_2\text{O}_3$

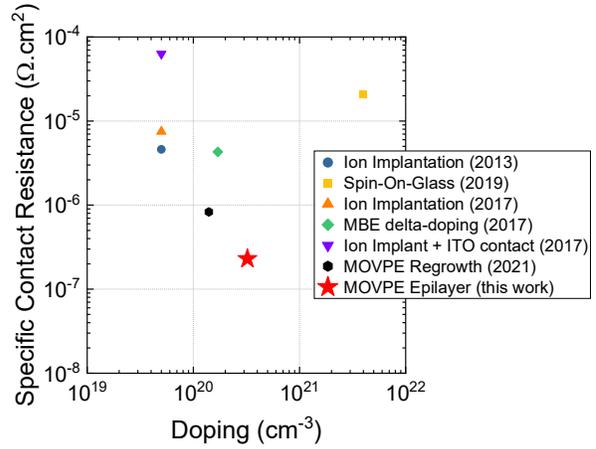


Figure 2 – Benchmark of reported $\beta\text{-Ga}_2\text{O}_3$ specific contact resistance values

	Electron Concentration n (cm^{-3})	n^+ GO Thickness (nm)	Sheet Resistance (Ω/\square)	Pre-Anneal Specific Contact Resistance ρ_c ($\Omega\cdot\text{cm}^2$)	Post-Anneal Specific Contact Resistance ρ_c ($\Omega\cdot\text{cm}^2$)
$\beta\text{-Ga}_2\text{O}_3$	1.77×10^{20}	145	96.6	2.12×10^{-6}	6.11×10^{-7}
	2.51×10^{20}	65	71.8	1.67×10^{-6}	2.48×10^{-7}
	3.23×10^{20}	170	29.8	1.12×10^{-7}	2.30×10^{-7}
$\beta\text{-(Al}_{0.12}\text{Ga}_{0.88})_2\text{O}_3$	1.23×10^{20}	76	216	6.96×10^{-6}	2.18×10^{-6}
$\beta\text{-(Al}_{0.16}\text{Ga}_{0.84})_2\text{O}_3$	1.22×10^{20}	111	284	3.56×10^{-5}	5.77×10^{-5}
$\beta\text{-(Al}_{0.22}\text{Ga}_{0.78})_2\text{O}_3$	5.49×10^{19}	83.5	608	2.01×10^{-4}	4.56×10^{-4}

Table 1 – Electrical Properties and epilayer thicknesses of $\beta\text{-Ga}_2\text{O}_3$ and $\beta\text{-(Al}_x\text{Ga}_{1-x})_2\text{O}_3$ structures

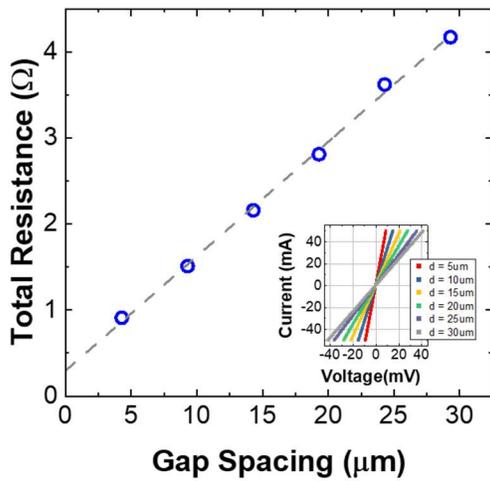


Figure 3 – TLM measurement and I-V curve of lowest specific resistance Ga_2O_3 sample

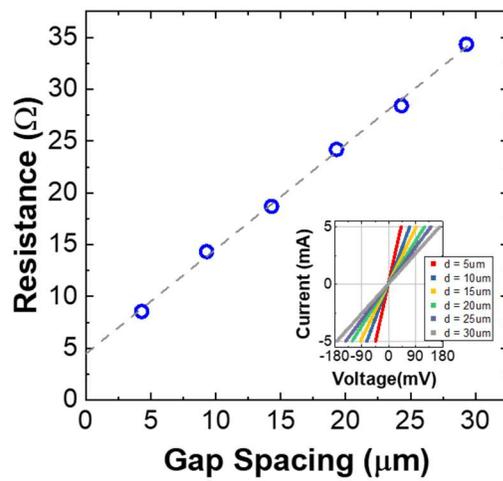


Figure 4 – TLM measurement and I-V curve of lowest specific resistance $\beta\text{-(Al}_{.12}\text{Ga}_{.88})_2\text{O}_3$ sample